

# Models development of new cells protection for electrostatic discharges integrated in Smart Power technology

In collaboration with:



Alma Mater Studiorum – University of Bologna  
ARCES (Advanced Research Center on Electronic System)

EIT4SEMM XXXVI cycle- PHD student yearly assessment

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**Co-advisor:** Prof. Elena Gnani

# State of art:

## On-chip ESD protection for Internet of Things (IoT)

- 50 billion devices connected to internet
- Endless possibilities in combining

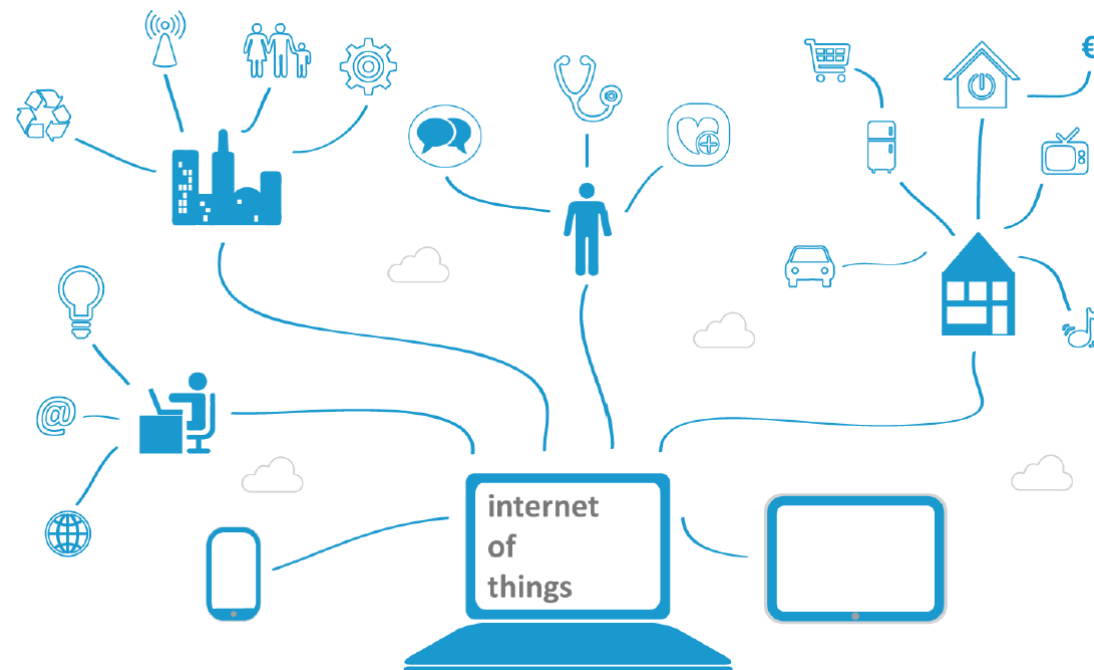
➤ Sensors



➤ Actuators



➤ Networked intelligence



- Productivity (Automotive industries, Manufacturing, retail environments, logistics and navigation)
- Save resources (Cities, homes, )
- Prevent health issues (human, worksites, transportations, factories)

**Many of the applications in IoT require non-standard on-chip ESD protection clamps**



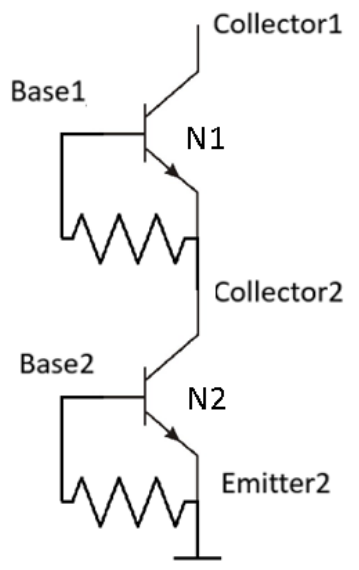
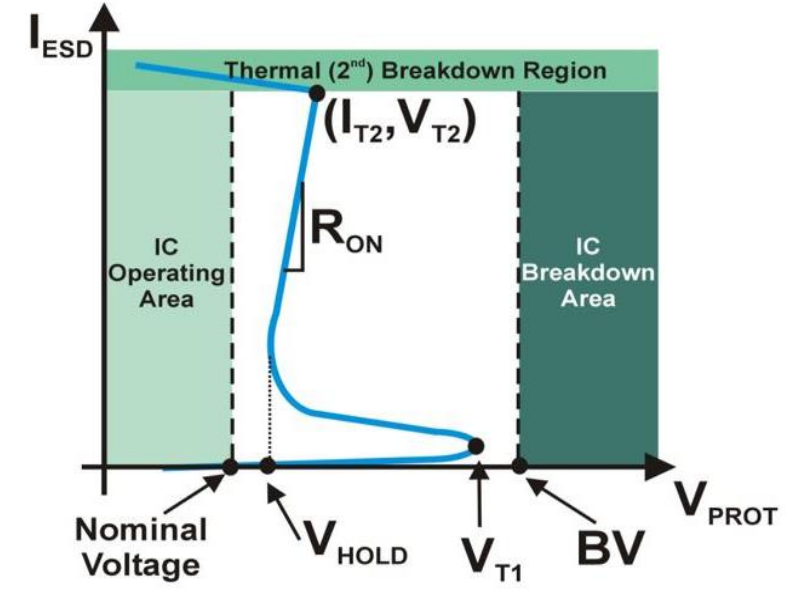
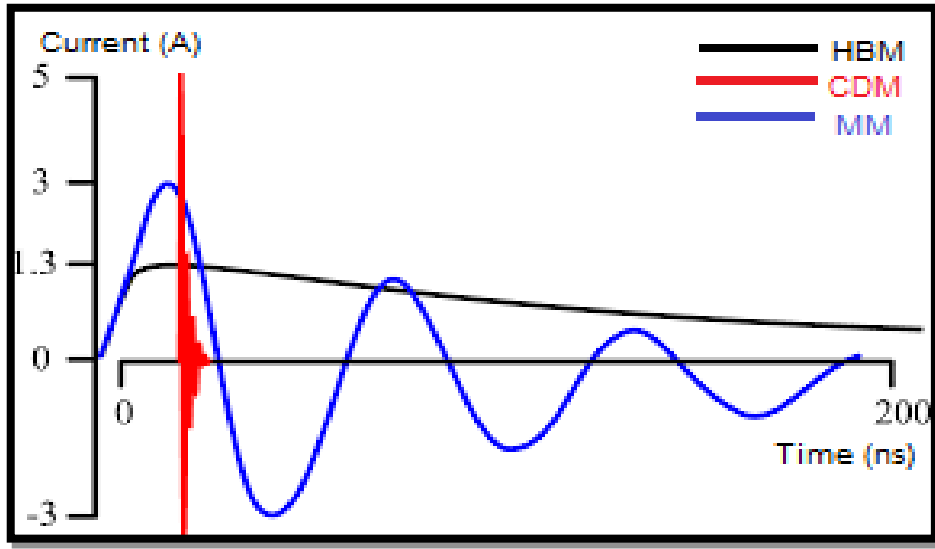
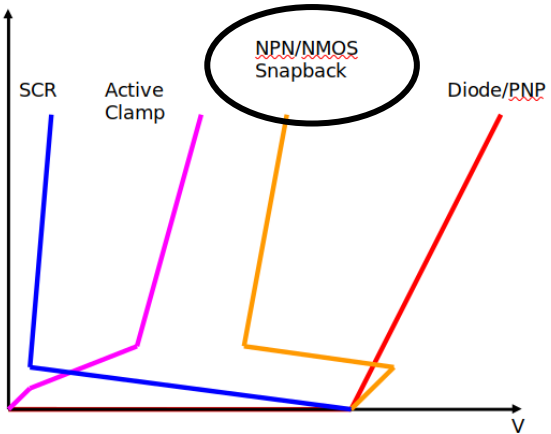
## Goal

Simulate different possible stress tests over the original ESD protection under test

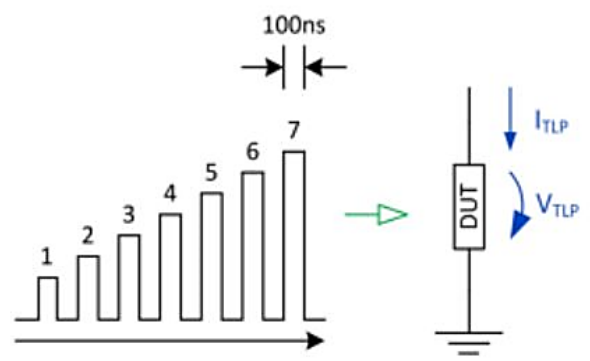
## Summary

- Background knowledge
- From layout to TCAD (Technology Computer Aided Design)
- TLP (Transmission Line Pulse) characterization
- Power to failure:
  - Test
  - How to improve performances
- Conclusions

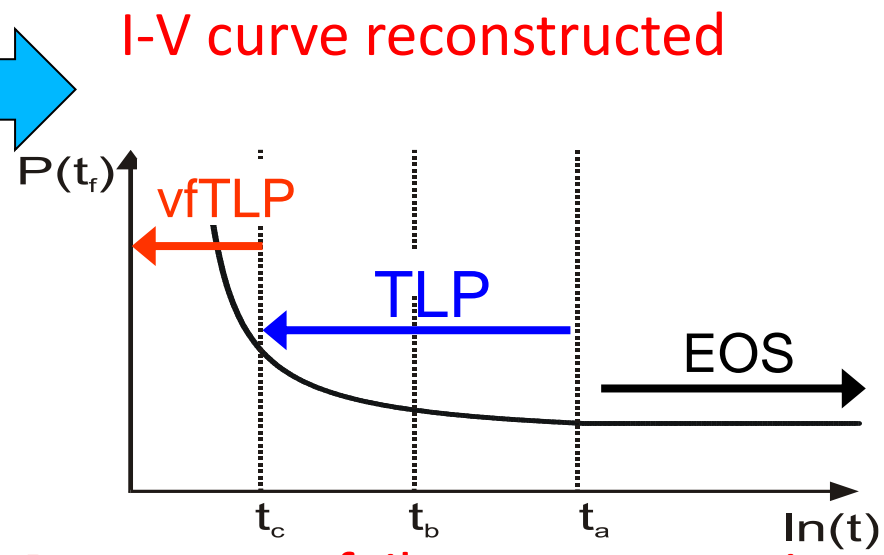
# Background Knowledge – ESD common clamps vs. Bipolar transistors under ESD conditions



DUT



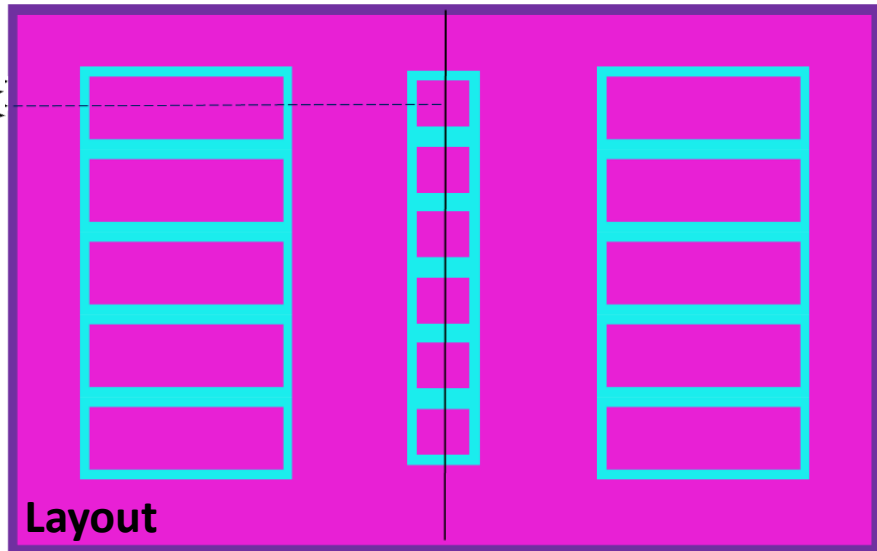
Stress pulses to be modeled



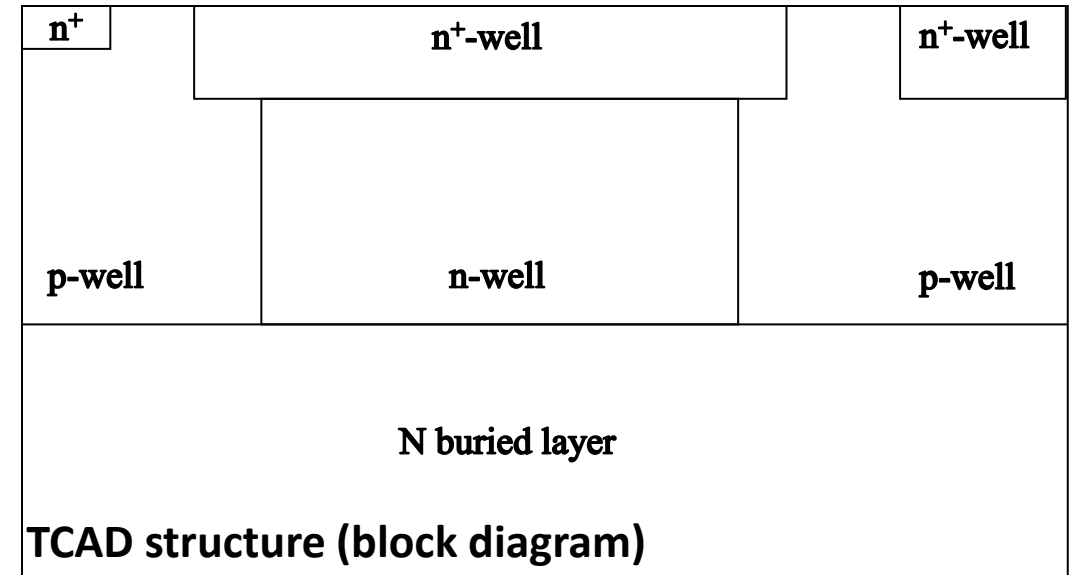
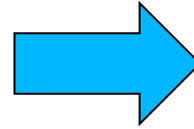
Power- to – failure vs. stress time

I-V curve reconstructed

# From layout to TCAD (Technology Computer Aided Design)



Trench  
N-well  
P-well

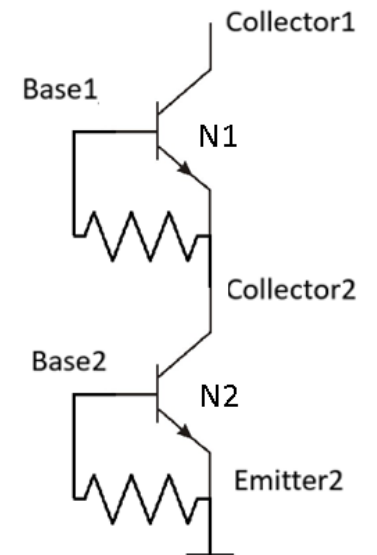


## Layout structure:

- Symmetric with respect to the center
- BiCMOS technology implementation

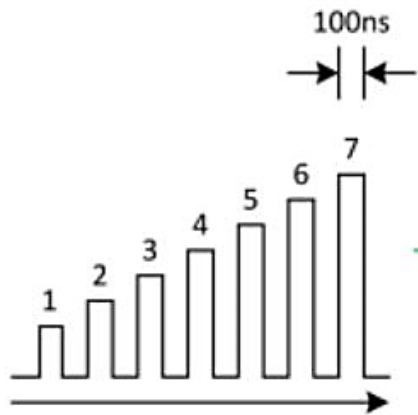
## TCAD structure:

- 2D structure sufficient according to layout dimensions
- Doping profiles tuned with the device fabrication process
- Selected Physical models to implement impact ionization and thermodynamic behavior of the device

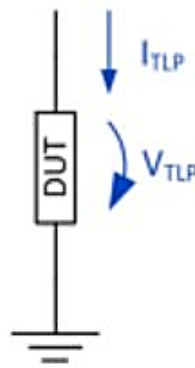


Schematic

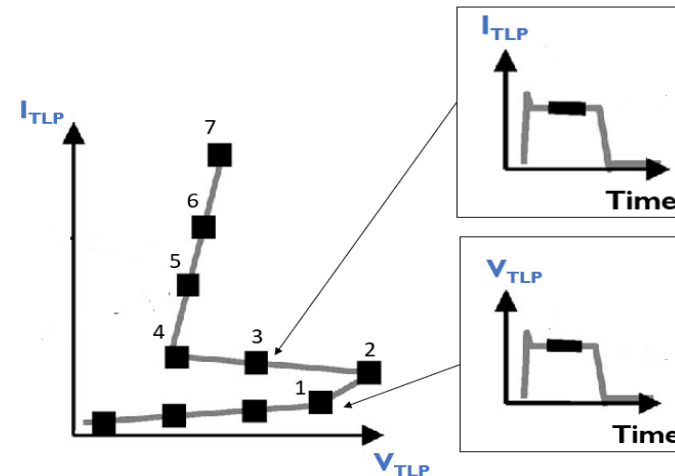
# TLP (Transmission Line Pulse) characterization



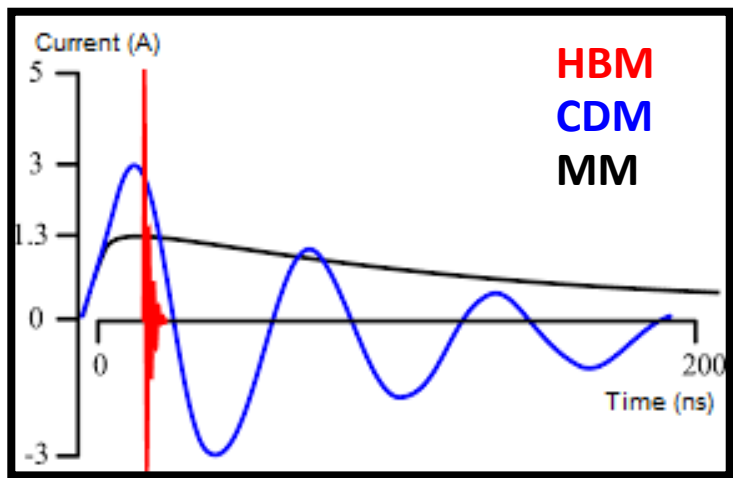
Step 1



Step 2



I-V curve reconstruction

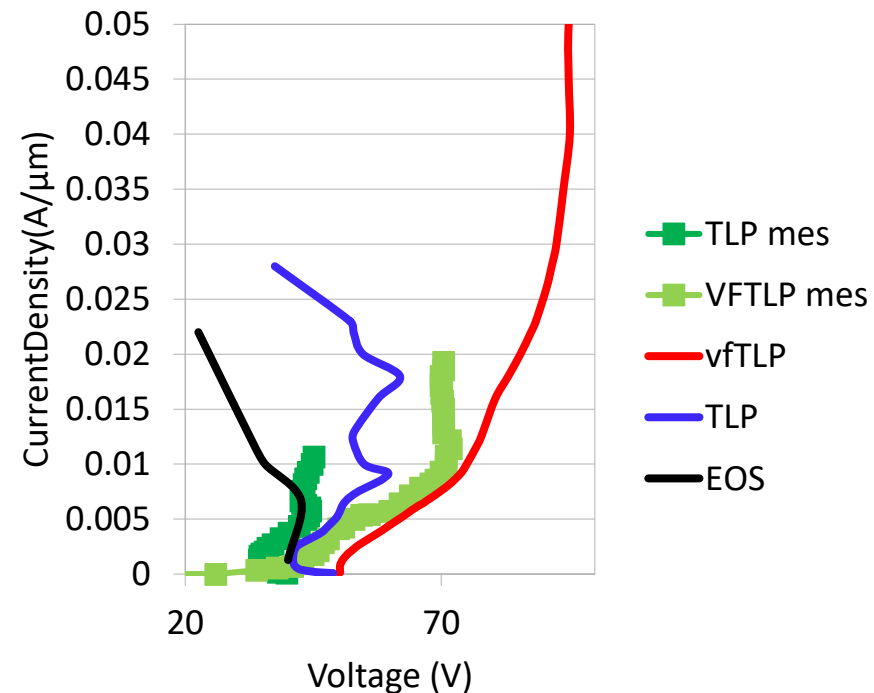
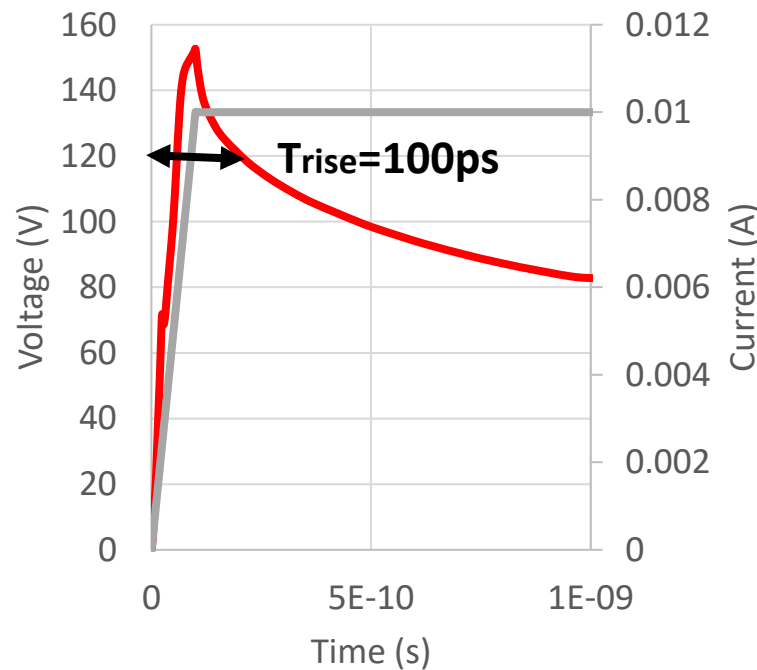


➤ **HBM: very fast TLP ( $T_{pulse}=1ns$ )**

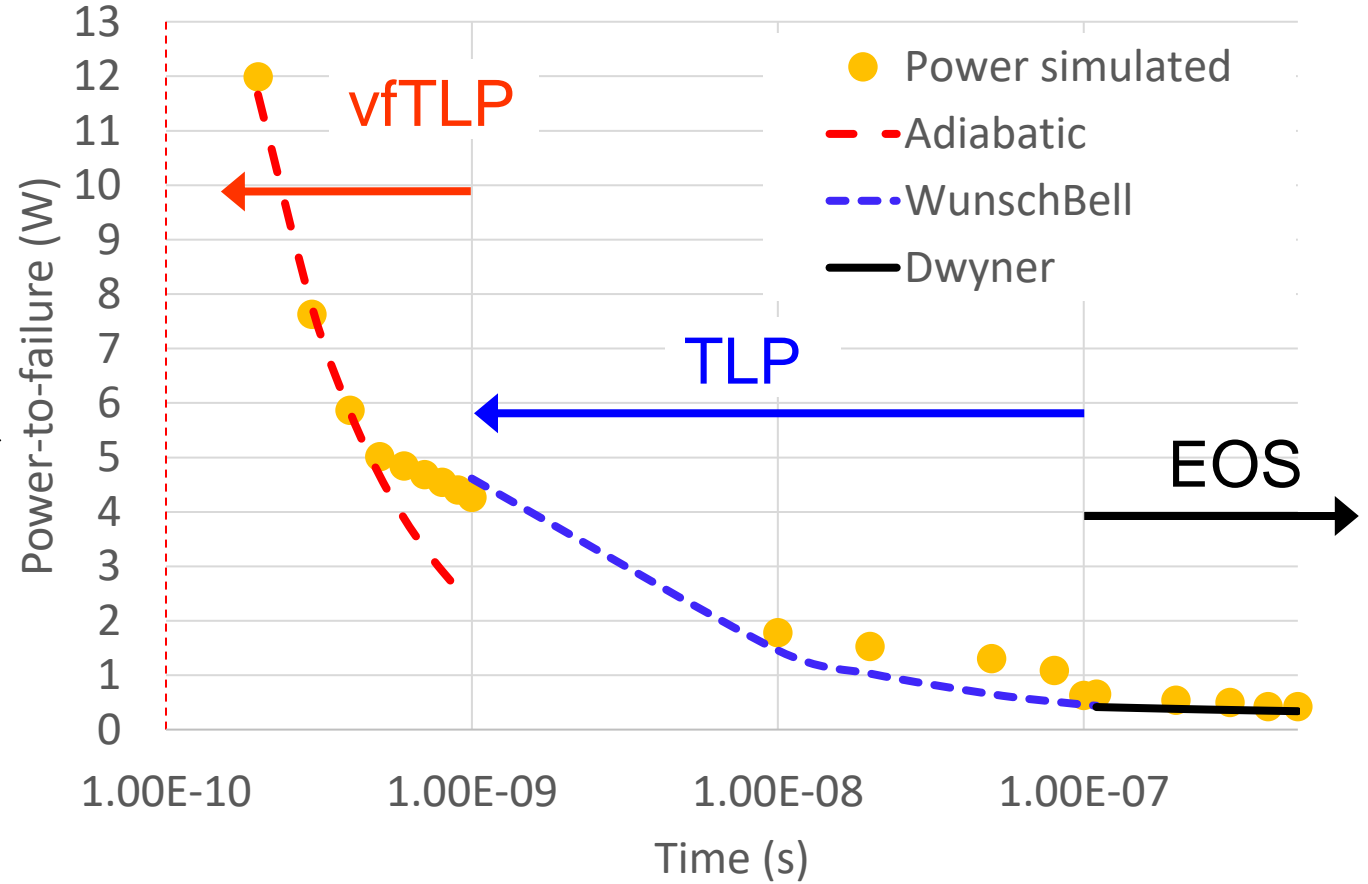
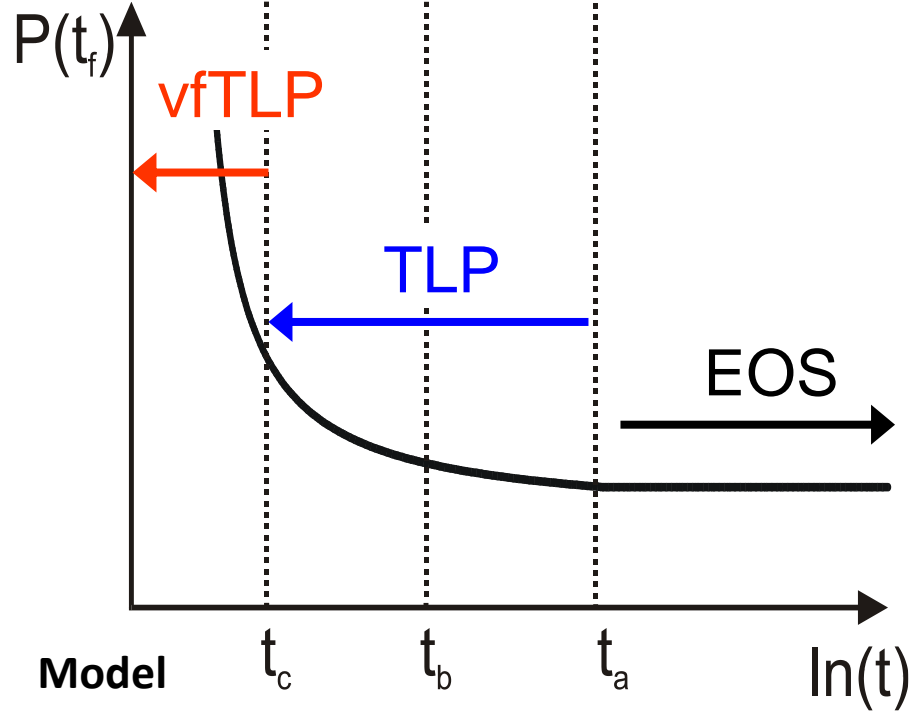
➤ **CDM: TLP ( $T_{pulse}=100ns$ )**

➤ **MM: EOS ( $T_{pulse}=500ns$ )**

**vfTLP**

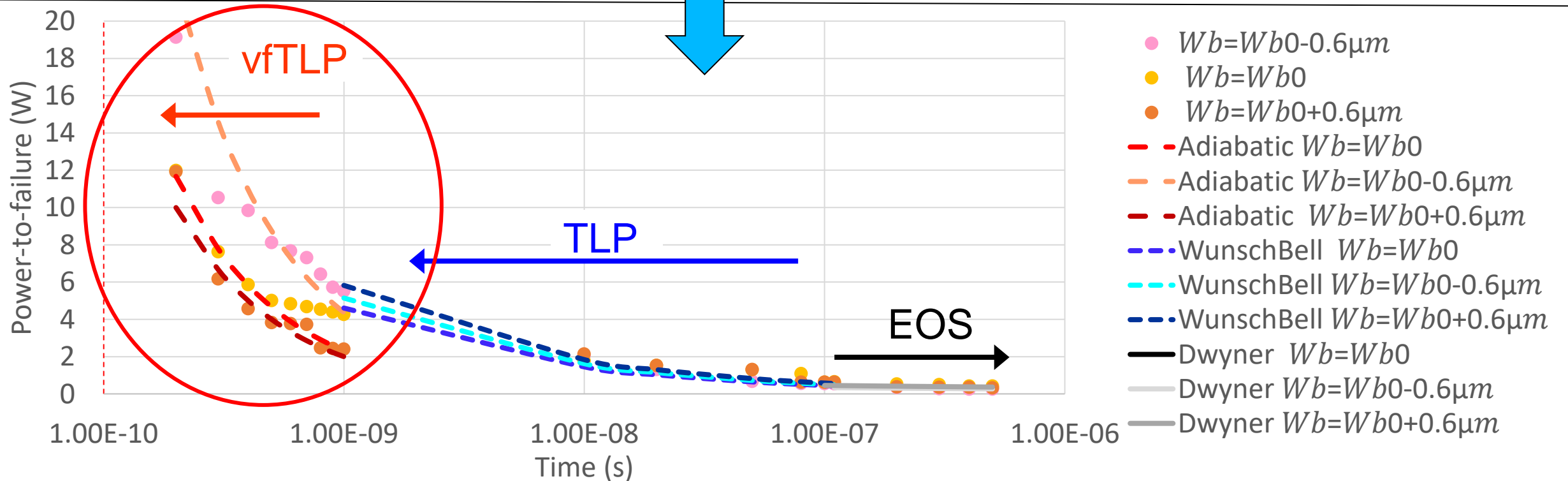
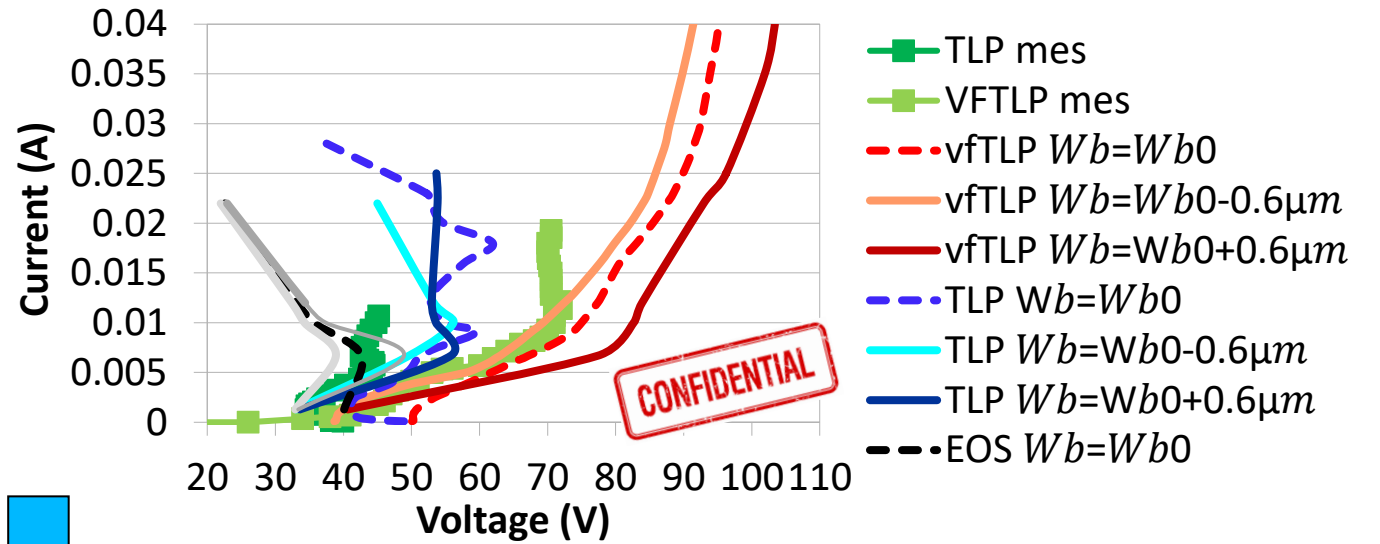
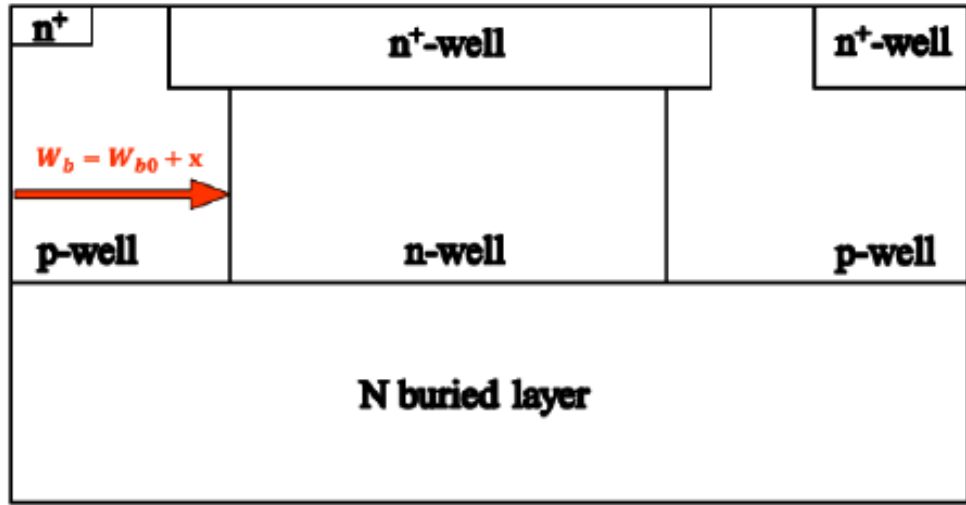


# Power – to – Failure test



- Power<sub>Failure</sub> ( $t_f$ ) =  $I_{failure} * V_{failure}$** 
  - $I_{failure}$  and  $V_{failure}$  are calculated using as **Failure Criterion** a maximum Temperature close to Silicon temperature melting  $\geq 1200K$
  - For each time pulse, the criterion has been applied in order to reconstruct the device behavior in terms of possible failure levels in the three regions (vfTLP, TLP and EOS)

# Power – to – Failure: how to improve performances

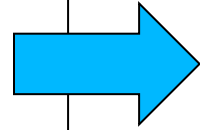
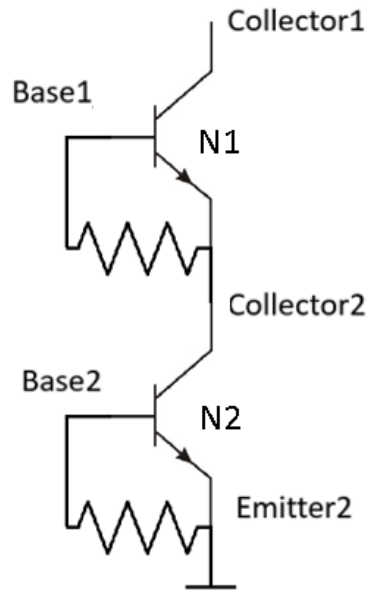




# Conclusions

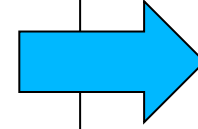
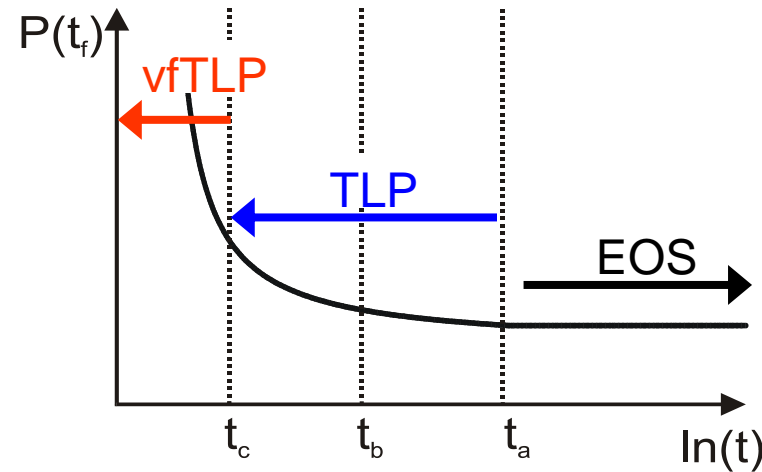
## New technology:

Two low voltage BJTs to build an high voltage ESD protection



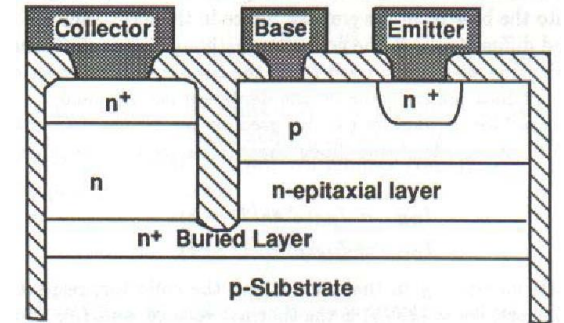
## New Approach:

Temperature/Hot Spots failure criterion to predict very fast TLP stress performances

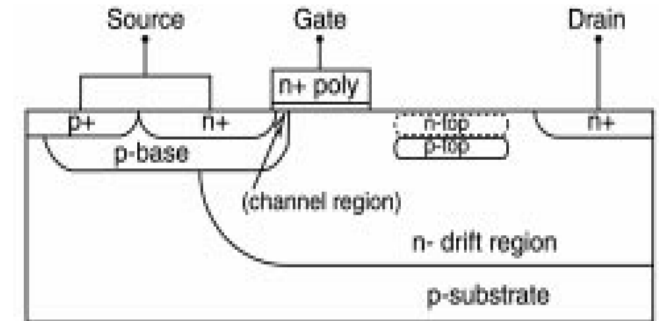


## Future work:

Test the new approach in a different device based on LDMOS (planar double-diffused MOS) technology



BiCMOS technology



LDMOS technology

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Word cloud featuring the phrase "thank you" in various languages and scripts, including: danke, 謝謝, ngiyabonga, teşekkür ederim, gracias, thank you, obrigado, merci, and many others.

